

TN Columbus \* \* \* \* \*

FILE 'HOME' ENTERED AT 17:07:05 ON 30 AUG 2005

=> FIL STNGUIDE

COST IN U.S. DOLLARS

SINCE FILE  
ENTRY

TOTAL  
SESSION

FULL ESTIMATED COST

0.21

0.21

FILE 'STNGUIDE' ENTERED AT 17:07:12 ON 30 AUG 2005

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AND TECHNOLOGY CORPORATION, AND FACHINFORMATIONSZENTRUM KARLSRUHE

FILE CONTAINS CURRENT INFORMATION.

LAST RELOADED: Aug 26, 2005 (20050826/UP).

=> file pnttext

COST IN U.S. DOLLARS

SINCE FILE  
ENTRY

TOTAL  
SESSION

FULL ESTIMATED COST

0.06

0.27

FILE 'EPFULL' ENTERED AT 17:07:20 ON 30 AUG 2005

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FILE 'FRFULL' ENTERED AT 17:07:20 ON 30 AUG 2005

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FILE 'PATDPAFULL' ENTERED AT 17:07:20 ON 30 AUG 2005

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FILE 'PCTFULL' ENTERED AT 17:07:20 ON 30 AUG 2005

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FILE 'RDISCLOSURE' ENTERED AT 17:07:20 ON 30 AUG 2005

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FILE 'USPATFULL' ENTERED AT 17:07:20 ON 30 AUG 2005

CA INDEXING COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPAT2' ENTERED AT 17:07:20 ON 30 AUG 2005

CA INDEXING COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY (ACS)

=> s polyoxymethylene and formaldehyde and catalyst#

6 FILES SEARCHED...

L1 2336 POLYOXYMETHYLENE AND FORMALDEHYDE AND CATALYST#

=> s l1 and cyclooctadiene

L2 28 L1 AND CYCLOOCTADIENE

=> s l2 and tetrahydrofuran

L3 11 L2 AND TETRAHYDROFURAN

=> s l3 and ligand#

L4 6 L3 AND LIGAND#

=> s l3 and (pentamethylcyclopentadienyl or pentamethyl cyclopentadienyl)

L5 1 L3 AND (PENTAMETHYLCYCLOPENTADIENYL OR PENTAMETHYL CYCLOPENTADIENYL)

=> d

L5 ANSWER 1 OF 1 USPATFULL on STN

AN 2005:203498 USPATFULL

TI Production of polyoxymethylene and suitable catalysts

IN Gortz, Hans-Helmut, Freinshein, GERMANY, FEDERAL REPUBLIC OF

Luinstra, Gerrit, Mannheim, GERMANY, FEDERAL REPUBLIC OF  
Forster, Monika, Muhlthal, GERMANY, FEDERAL REPUBLIC OF  
Baumann, Andreas, Nurtlingen, GERMANY, FEDERAL REPUBLIC OF  
Lindner, Ekkehard, Tubingen, GERMANY, FEDERAL REPUBLIC OF

PI US 2005176924 A1 20050811  
AI US 2003-510475 A1 20030410 (10)  
WO 2003-EP3746 20030410  
PRAI DE 2003-102159785 20020411  
DT Utility  
FS APPLICATION  
LN.CNT 618  
INCL INCLM: 528/425.000  
NCL NCLM: 528/425.000  
IC [7]  
ICM: C08G065-34

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

=> d 13 1-11

L3 ANSWER 1 OF 11 EPFULL COPYRIGHT 2005 EPO/FIZ KA on STN

AN 2005:1622 EPFULL EDP 20050727 ED 20050727 UP 20050727  
DUPD 20050727 DUPW 200530  
TIEN Lithographic printing plate precursor and lithographic printing method.  
TIFR Precurseur de plaque d'impression lithographique et methode pour  
l'impression lithographique.  
TIDE Flachdruckplattenvorlaeufer und Flachdruckverfahren.  
IN Inno, Toshifumi, Fuji Photo Film Co., Ltd., 4000, Kawashiri,  
Yoshida-cho, Haibara-gun, Shizuoka, JP;  
Oshima, Yasuhito, Fuji Photo Film Co., Ltd., 4000, Kawashiri,  
Yoshida-cho, Haibara-gun, Shizuoka, JP;  
Kakino, Ryuki, Fuji Photo Film Co., Ltd., 4000, Kawashiri,  
Yoshida-cho, Haibara-gun, Shizuoka, JP  
PA Fuji Photo Film Co., Ltd., 210, Nakanuma, Minami-Ashigara-shi,  
Kanagawa, JP  
PAN 2602262  
AG HOFFMANN - EITLE, Patent- und Rechtsanwaelte Arabellastrasse 4, 81925  
Muenchen, DE  
AGN 101511  
LAF English  
LA English  
LAP English  
TL German; English; French  
DT Patent  
PIT EPA2 Application published without search report  
PI EP 1557262 A2 20050727  
DS AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HU IE IS IT LI LT LU MC NL PL  
PT RO SE SI SK TR  
AI EP 2005-1195 A 20050121  
PRAI JP 2004-15723 A 20040123  
JP 2004-15766 A 20040123  
JP 2004-86566 A 20040324  
IC.VER 7  
ICM B41C001-10  
ICS B41M005-30; B41M005-28

AN 2005:1622 EPFULL EDP 20050727 ED 20050810 UP 20050810  
DUPD 20050810 DUPW 200532  
TIEN Lithographic printing plate precursor and lithographic printing method.  
TIFR Precurseur de plaque d'impression lithographique et methode pour  
l'impression lithographique.  
TIDE Flachdruckplattenvorlaeufer und Flachdruckverfahren.  
IN Inno, Toshifumi, Fuji Photo Film Co., Ltd., 4000, Kawashiri,  
Yoshida-cho, Haibara-gun, Shizuoka, JP;  
Oshima, Yasuhito, Fuji Photo Film Co., Ltd., 4000, Kawashiri,  
Yoshida-cho, Haibara-gun, Shizuoka, JP;  
Kakino, Ryuki, Fuji Photo Film Co., Ltd., 4000, Kawashiri,  
Yoshida-cho, Haibara-gun, Shizuoka, JP

PA Fuji Photo Film Co., Ltd., 210, Nakanuma, Minami-Ashigara-shi,  
Kanagawa, JP  
PAN 2602262  
AG HOFFMANN - EITLE, Patent- und Rechtsanwaelte Arabellastrasse 4, 81925  
Muenchen, DE  
AGN 101511  
LAF English  
LA English  
LAP English  
TL German; English; French  
DT Patent  
PIT EPA3 Separate publication of search report  
PI EP 1557262 A3 20050810  
DS AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HU IE IS IT LI LT LU MC NL PL  
PT RO SE SI SK TR  
AI EP 2005-1195 A 20050121  
PRAI JP 2004-15723 A 20040123  
JP 2004-15766 A 20040123  
JP 2004-86566 A 20040324  
IC.VER 7  
ICM B41C001-10  
ICS B41M005-30; B41M005-28

L3 ANSWER 2 OF 11 EPFULL COPYRIGHT 2005 EPO/FIZ KA on STN

AN 1995:38854 EPFULL UP 20050511  
DUPD 20050511 DUPW 200519  
TIEN NOVEL RESIN COMPOSITION.  
TIFR NOUVELLE COMPOSITION DE RESINE.  
TIDE NEUE HARZZUSAMMENSETZUNG.  
IN NATORI, Itaru, Room No. 405, Sukaihaimu, 817-3, Tookaichibamachi,  
Midori-ku, Yokohama-shi, Kanagawa-ken 227, JP;  
IMAIZUMI, Kimio, Room No. 208, Kanetsuka Mansion, 280-3, Noshio  
5-chome, Kiyose-shi, Tokyo 204, JP;  
KATO, Kiyoo, Room 101, Domiiru-Kaishima 3-18-15, Shimokodanaka,  
Nakahara-ku, Kawasaki-shi, Kanagawa-ken 211, JP  
PA Asahi Kasei Kabushiki Kaisha, 2-6, Dojimahama 1-chome, Kita-ku,  
Osaka-shi, Osaka, JP  
PAN 219577  
AG Blake, John Henry Francis, et al, Brookes Batchellor 102-108 Clerkenwell  
Road, London EC1M 5SA, GB  
AGN 28375  
LAF Japanese  
LA English  
LAP English  
TL German; English; French  
DT Patent  
PIT EPA1 Application published with search report  
PI EP 743341 A1 19961120  
WO 9521217 19950810  
DS DE FR GB  
AI EP 1995-900930 A 19941121  
WO 1994-JP1970 A 19941121  
PRAI JP 1994-10567 A 19940201  
IC.VER 7  
ICM C08L045-00

L3 ANSWER 3 OF 11 GBFULL COPYRIGHT 2005 Univentio on STN

AN 2311071 GBFULL ED 20041103  
TI Curable resin and composition  
IN NATORI, ITARU; WATANABE, TOMONARI  
PA ASAHI KASEI KOGYO KABUSHIKI KAISHA  
PA.CNY JP  
DT Patent  
PIT GBA Application published  
PI GB 2311071 A 19970917  
AI GB 1997-10454 A 19951121  
PRAI WO 1995-JP2375 A 19951121  
JP 1994-286899 A 19941121

ICM C08F008-00  
ICS C08F297-02; C08G059-02; C08L045-00; C09D145-00; C09J145-00

L3 ANSWER 4 OF 11 PCTFULL COPYRIGHT 2005 Univentio on STN  
AN 2004072168 PCTFULL ED 20040901 EW 200435  
TIEN RESIN COMPOSITIONS  
TIFR COMPOSITIONS DE RESINE  
IN SCHMIDT, Hans-Werner, Lisztstrasse 26, 95444 Bayreuth, DE [DE, DE];  
BLOMENHOFER, Markus, Kanzleistrasse 54, 96328 Kueps-Johannisthal, DE  
[DE, DE];  
STOLL, Klaus, Am Sonnenrain 18, 79589 Binzen, DE [DE, DE];  
MEIER, Hans-Rudolf, Muespacherstrasse 74, CH-4055 Basel, CH [CH, CH]  
PA CIBA SPECIALTY CHEMICALS HOLDING INC., Klybeckstrasse 141, CH-4057  
Basel, CH [CH, CH], for all designates States except US;  
SCHMIDT, Hans-Werner, Lisztstrasse 26, 95444 Bayreuth, DE [DE, DE], for  
US only;  
BLOMENHOFER, Markus, Kanzleistrasse 54, 96328 Kueps-Johannisthal, DE  
[DE, DE], for US only;  
STOLL, Klaus, Am Sonnenrain 18, 79589 Binzen, DE [DE, DE], for US only;  
MEIER, Hans-Rudolf, Muespacherstrasse 74, CH-4055 Basel, CH [CH, CH],  
for US only  
AG CIBA SPECIALTY CHEMICALS HOLDING INC., Patent Department, Klybeckstrasse  
141, CH-4057 Basel, CH  
LAF English  
LA English  
DT Patent  
PI WO 2004072168 A2 20040826  
DS W: AE AG AL AM AT AU AZ BA BB BG BR BW BY BZ CA CH CN CO CR  
CU CZ DE DK DM DZ EC EE EG ES FI GB GD GE GH GM HR HU ID  
IL IN IS JP KE KG KP KR KZ LC LK LR LS LT LU LV MA MD MG  
MK MN MW MX MZ NA NI NO NZ OM PG PH PL PT RO RU SC SD SE  
SG SK SL SY TJ TM TN TR TT TZ UA UG US UZ VC VN YU ZA ZM  
ZW  
W-U: AE AL AM AT AZ BG BR BY BZ CN CO CR CZ DE DK EC EE ES FI  
GE HU JP KE KG KP KR KZ LS MD MX MZ NI PH PL PT RU SK SL  
TJ TR TT UA UG UZ YU  
RW (ARIPO): BW GH GM KE LS MW MZ SD SL SZ TZ UG ZM ZW  
RW (EAPO): AM AZ BY KG KZ MD RU TJ TM  
RW (EPO): AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HU IE IT LU MC  
NL PT RO SE SI SK TR  
RW (OAPI): BF BJ CF CG CI CM GA GN GQ GW ML MR NE SN TD TG  
RW-U (OAPI): BF BJ CF CG CI CM GA GN GQ GW ML MR NE SN TD TG  
AI WO 2004-EP50095 A 20040209  
PRAI EP 2003-03405084.9 20030214  
EP 2003-03103835.9 20031016  
ICM C08K005-20  
ICS C08K005-00

L3 ANSWER 5 OF 11 USPATFULL on STN  
AN 2005:203498 USPATFULL  
TI Production of **polyoxymethylene** and suitable **catalysts**  
IN Gortz, Hans-Helmut, Freinshein, GERMANY, FEDERAL REPUBLIC OF  
Luinstra, Gerrit, Mannheim, GERMANY, FEDERAL REPUBLIC OF  
Forster, Monika, Muhlthal, GERMANY, FEDERAL REPUBLIC OF  
Baumann, Andreas, Nurlingen, GERMANY, FEDERAL REPUBLIC OF  
Lindner, Ekkehard, Tübingen, GERMANY, FEDERAL REPUBLIC OF  
PI US 2005176924 A1 20050811  
AI US 2003-510475 A1 20030410 (10)  
WO 2003-EP3746 20030410  
PRAI DE 2003-102159785 20020411  
DT Utility  
FS APPLICATION  
LN.CNT 618  
INCL INCLM: 528/425.000  
NCL NCLM: 528/425.000  
IC [7]  
ICM: C08G065-34  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L3 ANSWER 6 OF 11 USPATFULL on STN  
AN 2005:196141 USPATFULL  
TI Lithographic printing plate precursor and lithographic printing method  
IN Inno, Toshifumi, Haibara-gun, JAPAN  
Oshima, Yasuhito, Haibara-gun, JAPAN  
Kakino, Ryuki, Haibara-gun, JAPAN  
PA Fuji Photo Film Co., Ltd. (non-U.S. corporation)  
PI US 2005170282 A1 20050804  
AI US 2005-38139 A1 20050121 (11)  
PRAI JP 2004-15723 20040123  
JP 2004-15766 20040123  
JP 2004-86566 20040324  
DT Utility  
FS APPLICATION  
LN.CNT 4302  
INCL INCLM: 430/270.100  
NCL NCLM: 430/270.100  
IC [7]  
ICM: G03C001-76  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L3 ANSWER 7 OF 11 USPATFULL on STN  
AN 2001:163300 USPATFULL  
TI Addition-crosslinking compositions which give heat-stable silicone rubber  
IN Achenbach, Frank, Simbach a. Inn, Germany, Federal Republic of  
Barthel, Herbert, Emmerting, Germany, Federal Republic of  
PA Wacker-Chemie GmbH, Munchen, Germany, Federal Republic of (non-U.S. corporation)  
PI US 6294635 B1 20010925  
AI US 1995-381809 19950201 (8)  
PRAI DE 1994-4405245 19940218  
DT Utility  
FS GRANTED  
LN.CNT 1143  
INCL INCLM: 528/015.000  
INCLS: 524/403.000; 525/474.000; 525/475.000  
NCL NCLM: 528/015.000  
NCLS: 524/403.000; 525/474.000; 525/475.000  
IC [7]  
ICM: C08G077-06  
EXF 524/403; 528/15; 525/474; 525/475  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L3 ANSWER 8 OF 11 USPATFULL on STN  
AN 2000:102371 USPATFULL  
TI Curable resin and resin composition comprising the same  
IN Watanabe, Tomonari, Yamato, Japan  
Natori, Itaru, Yokohama, Japan  
PA Asahi Kasei Kogyo Kabushiki Kaisha, Osaka, Japan (non-U.S. corporation)  
PI US 6100339 20000808  
WO 9616091 19960530  
AI US 1997-836757 19970521 (8)  
WO 1995-JP2375 19951121  
19970521 PCT 371 date  
19970521 PCT 102(e) date  
PRAI JP 1994-286899 19941121  
DT Utility  
FS Granted  
LN.CNT 3495  
INCL INCLM: 525/216.000  
INCLS: 525/098.000; 525/102.000; 525/105.000; 525/106.000; 525/123.000;  
525/194.232; 525/297.000; 525/310.000; 525/314.000; 525/332.100;  
525/332.800; 525/332.900; 525/338.000; 525/342.000; 525/350.000;  
525/353.000; 525/375.000; 525/376.000; 525/379.000; 525/385.000;  
525/386.000; 524/554.000  
NCL NCLM: 525/216.000  
NCLS: 524/554.000; 525/098.000; 525/102.000; 525/105.000; 525/106.000;  
525/123.000; 525/297.000; 525/310.000; 525/314.000; 525/332.100;

525/332.800; 525/332.900; 525/338.000; 525/342.000; 525/350.000;  
525/353.000; 525/375.000; 525/376.000; 525/379.000; 525/385.000;  
525/386.000

IC [7]

ICM: C08L053-02

ICS: C08L047-00

EXF 525/194; 525/216; 525/297; 525/314; 525/332.1; 525/332.3; 525/332.9;  
525/342; 525/350; 525/353; 525/232; 525/338; 525/375; 525/376; 525/379;  
525/385; 525/386; 525/98; 525/102; 525/105; 525/106; 525/123; 524/554

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L3 ANSWER 9 OF 11 USPATFULL on STN

AN 1999:34093 USPATFULL

TI Resin composition

IN Natori, Itaru, Yokohama, Japan

Imaizumi, Kimio, Kiyose, Japan

Kato, Kiyoo, Kawasaki, Japan

PA Asahi Kasei Kogyo Kabushiki Kaisha, Osaka, Japan (non-U.S. corporation)

PI US 5883192 19990316

WO 9521217 19950810

AI US 1996-663175 19960610 (8)

WO 1994-JP1970 19941121

19960610 PCT 371 date

19960610 PCT 102(e) date

PRAI JP 1994-10567 19940201

DT Utility

FS Granted

LN.CNT 3226

INCL INCLM: 525/098.000

INCLS: 525/096.000; 525/099.000; 525/211.000; 525/216.000

NCL NCLM: 525/098.000

NCLS: 525/096.000; 525/099.000; 525/211.000; 525/216.000

IC [6]

ICM: C08L053-00

EXF 525/211; 525/216; 525/96; 525/98; 525/99

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L3 ANSWER 10 OF 11 USPATFULL on STN

AN 91:56827 USPATFULL

TI Method of metalizing a surface using a mixture of olefin and  
dibenzalacetone palladium complex

IN Finter, Jorgen, Freiburg, Germany, Federal Republic of

PA Ciba-Geigy Corporation, Ardsley, NY, United States (U.S. corporation)

PI US 5032488 19910716

AI US 1988-165448 19880301 (7)

RLI Continuation of Ser. No. US 1986-895978, filed on 13 Aug 1986, now  
abandoned

PRAI CH 1985-3645 19850823

DT Utility

FS Granted

LN.CNT 582

INCL INCLM: 430/270.000

INCLS: 430/281.000; 430/283.000; 430/284.000; 430/285.000; 430/324.000;

430/325.000; 430/423.000; 430/424.000; 522/034.000; 522/066.000;

522/152.000

NCL NCLM: 430/270.100

NCLS: 430/281.100; 430/283.100; 430/284.100; 430/285.100; 430/324.000;

430/325.000; 430/423.000; 430/424.000; 522/034.000; 522/066.000;

522/129.000; 522/152.000

IC [5]

ICM: G03C001-492

EXF 430/423; 430/424; 430/324; 430/325; 430/270; 430/281; 430/283; 430/284;

430/285; 522/34; 522/66; 522/152

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L3 ANSWER 11 OF 11 USPATFULL on STN

AN 85:13443 USPATFULL

TI Glycolaldehyde process

IN Auvil, Steven R., Macungie, PA, United States

Mills, Patrick L., Creve Coeur, MO, United States  
PA Monsanto Company, St. Louis, MO, United States (U.S. corporation)  
PI US 4503260 19850305  
AI US 1983-504001 19830613 (6)  
DT Utility  
FS Granted  
LN.CNT 822  
INCL INCLM: 568/462.000  
INCLS: 568/420.000; 568/458.000  
NCL NCLM: 568/462.000  
NCLS: 568/420.000; 568/458.000  
IC [3]  
ICM: C07C045-49  
EXF 568/458; 568/462; 568/420; 568/862  
CAS INDEXING IS AVAILABLE FOR THIS PATENT.

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